Refine Search

Search Results -

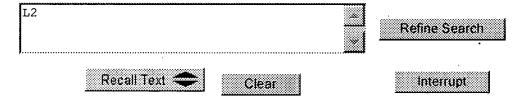
Terms	Documents
(resist or photoresist) and (fluorine or "nf.sub.3" or "cf.sub.4" or "c.sub.2f.sub.6" or "cf.sub.4") same plasma same (oxygen or "o.sub.2" or ozone or "o.sub.3") same ((low adj concentration) or percent)	122

US Pre-Grant Publication Full-Text Database US Patents Full-Text Database

Database:

US OCR Full-Text Database
EPO Abstracts Database
JPO Abstracts Database
Derwent World Patents Index
IBM Technical Disclosure Bulletins

Search:



Search History

DATE: Friday, April 15, 2005 Printable Copy Create Case

Set Name side by side	Query	<u>Hit</u> <u>Count</u>	Set Name result set
DB=	PGPB,USPT,USOC,EPAB,JPAB,DWPI,TDBD; PLUR=YES; OP=ADJ		
<u>L2</u>	(resist or photoresist) and (fluorine or "nf.sub.3" or "cf.sub.4" or "c.sub.2f.sub.6" or "cf.sub.4") same plasma same (oxygen or "o.sub.2" or ozone or "o.sub.3") same ((low adj concentration) or percent)	122	<u>L2</u>
<u>L1</u>	(fluorine or "nf.sub.3" or "cf.sub.4" or "c.sub.2f.sub.6" or "cf.sub.4") same plasma same (oxygen or "o.sub.2" or ozone or "o.sub.3") same ((low adj concentration) or percent)	210	<u>L1</u>

END OF SEARCH HISTORY